Vacuum 🕨 PVD Thin films 🕨 Leak testing 🕨 Plasma



Thin layer coating by evaporation

EVA 450



Simple and highly flexible the EVA450 guarantees success in your new developments.

Located halfway between **development and production** tool, this vacuum evaporator has been developed so as to offer multiple configurations. For instance :

- Mono or multi pockets sources
- Electron beam source
- Thermal source (Joule, effusion)
- Etc.

Thanks to its dimensions, several sources can be combined. Concerning substrate holder we offer either domes (simple or planetary motion) or functional single wafer. The thickness measurement is achieved using quartz crystal balance, remotely interfaced to the PLC sequences controller. This software allows to realize complex multilayers in automatic mode.



Main features

Vacuum chamber diameter :	450 mm
Height :	600 mm
Volume :	120 litres
Ultimate vacuum (turbomolecular configuration) :	5.10 ⁻⁷ mbar ^[1]
Ultimate vacuum (cryogenic configuration) :	5.10 ⁻⁸ mbar ^[1]
System throughput :	20 x dia. 100 mm
Planar uniformity :	< +/- 5% ^[1]
Through the wall installation :	Yes
Load lock :	Yes
Fully automatic system controller :	- Process management - Traceability

[1] These values have been measured on equipment we have delivered and should be handled as information only. The features of a system depend on its final configuration.



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